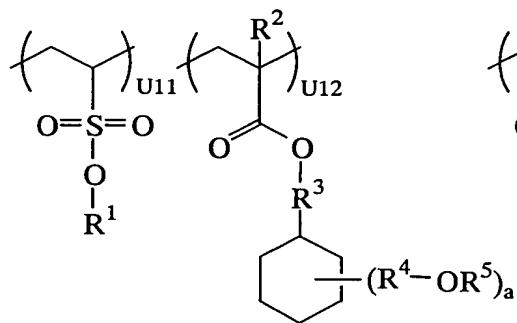
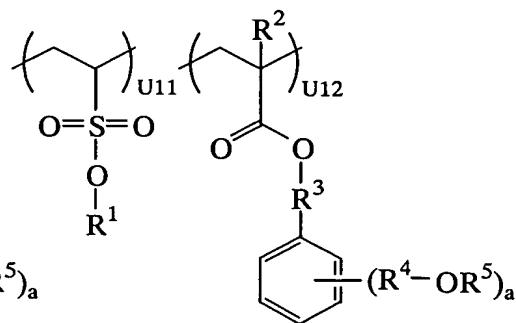


ABSTRACT

A polymer comprising recurring units of (1a) or (1b) 5 wherein R¹ is an acid labile group, adhesive group or fluoroalkyl, R² is H, F, alkyl or fluoroalkyl, R³ and R⁴ each are a single bond, alkylene or fluoroalkylene, R⁵ is H or an acid labile group, "a" is 1 or 2, 0 < U11 < 1 and 0 < U12 < 1 and having a Mw of 1,000-500,000 is used as a base resin to 10 formulate a resist composition which is sensitive to high-energy radiation, maintains high transparency at a wavelength of up to 200 nm, and has improved alkali dissolution contrast and plasma etching resistance.



(1a)



(1b)